

CORRECTION

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Correction: Interface-engineered reliable HfO₂-based RRAM for synaptic simulation

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Correction for 'Interface-engineered reliable HfO₂-based RRAM for synaptic simulation' by Qiang Wang *et al.*, *J. Mater. Chem. C*, 2019, DOI: 10.1039/c9tc04880d.

There was an error in the author list of this published article.

The corresponding authors for this paper are Gang Niu (gangniu@xjtu.edu.cn) and Wei Ren (wren@mail.xjtu.edu.cn). The footnote indicating that Qiang Wang and Gang Niu contributed equally to the work was not intended.

The corrected author list and notations are shown here.

The Royal Society of Chemistry apologises for these errors and any consequent inconvenience to authors and readers.

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